


| | | | |
|---|--|---------------------------------------|-------------------------------|
| Substitute Form PTO-1449 (Modified) Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b)) | U.S. Department of Commerce Patent and Trademark Office | Attorney's Docket No. 10559-863001 | Application No. 10/698,782 |
| | Applicant Rex K. Frost et al. | | |
| | Filing Date October 31, 2003 | Group Art Unit | |

| U.S. Patent Documents | | | | | | | |
|-----------------------|-----------|-----------------|------------------|--------------------|-------|----------|----------------------------|
| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
| <i>AR</i> | AA | 6,492,069 | 12/2002 | Wu, et al. | | | |
| <i>AR</i> | AB | 6,500,587 | 12/2002 | Ghandehari, et al. | | | |
| <i>AR</i> | AC | 6,524,752 | 02/2003 | Pierrat | | | |
| <i>AR</i> | AD | 6,524,755 | 02/2003 | Jin, et al. | | | |
| <i>AR</i> | AE | 6,569,580 | 05/2003 | Campi, et al. | | | |
| | AF | | | | | | |
| | AG | | | | | | |

| Foreign Patent Documents or Published Foreign Patent Applications | | | | | | | | |
|---|-----------|-----------------|------------------|--------------------------|-------|----------|-------------|----|
| Examiner Initial | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation | |
| | | | | | | | Yes | No |
| | AH | | | | | | | |
| | AI | | | | | | | |

| Other Documents (include Author, Title, Date, and Place of Publication) | | |
|---|-----------|---|
| Examiner Initial | Desig. ID | Document |
| <i>AR</i> | AJ | Liebmann, L., "Layout Impact of Resolution Enhancement Techniques: Impediment or Opportunity", <i>International Symposium on Physical Design 2003</i> , Session 7, pp. 110-117, Monterey, CA, April 6-9 (2003). |
| <i>AR</i> | AK | Liebmann, L., "Resolution Enhancement Techniques in Optical Lithography, It's not just a Mask Problem", <i>Proceedings SPIE, Photomask and Next-Generation Lithography Mask Technology VIII</i> , Vol. 4409, pp. 23-32 (2001). |
| <i>AR</i> | AL | Nordquist, K., et al., "Critical Dimension and Image Placement Issues for Step and Flash Imprint Lithography Templates", <i>Proceedings of SPIE, 22nd Annual BACUS Symposium on Photomask Technology</i> , Vol. 4889, No. 129, pp. 1143-1150 (2002). |
| <i>AR</i> | AM | Petersen, J., et al., "Development of a Sub-100nm Integrated Imaging System Using Chromeless Phase-Shifting Imaging with Very High NA KrF Exposure and Off-axis Illumination", <i>Proceedings SPIE, Design, Process Integration, and Characterization for Microelectronics</i> , Vol. 4692, pp. 298-311 (2002). |
| <i>AR</i> | AN | Scheid, G., et al., "Contact Holes: Optical Area Measurement Predicts Printability and is Highly Repeatable", presented at Photomask Japan 2001, Paper 4409-11, pp. 1-6 (2001). |
| <i>AR</i> | AO | Zhang, H., et al., "Compact Formulation of Mask Error Factor for Critical Dimension Control in Optical Lithography", <i>Proceedings SPIE, Metrology, Inspection, and Process Control for Microlithography XVI</i> , Vol. 4689, pp. 462-465 (2002). |
| | AP | |

| | |
|--|--------------------------|
| Examiner Signature  | Date Considered 10/06 |
| EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | |